

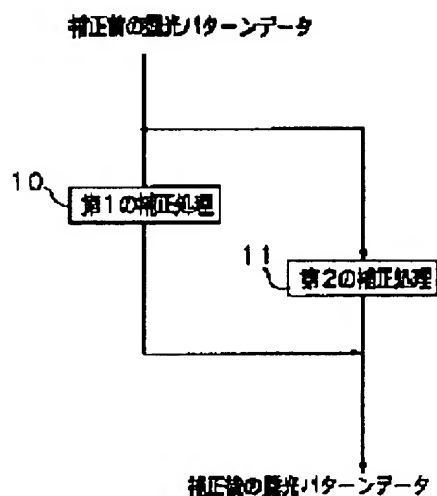
CORRECTION OF DATA FOR EXPOSURE PATTERN

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- **International:** H01L21/027; H01L21/02; (IPC1-7): H01L21/027
- **European:**
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Abstract of JP7094376

PURPOSE:To correct exposure pattern data without equipment dependence by combining the results of two independent corrective procedures. **CONSTITUTION:**Rectangular or non-rectangular patterns of various sizes, forming exposure pattern data, are subjected to a first corrective procedure 10 in consideration of exposure energy, exposure time, the size of pattern data, and pattern spacing. The patterns, not subjected to the first corrective procedure, are also subjected to a second corrective procedure 11 in consideration of thermal effects on the surface of an object. The results of both procedures are combined to obtain a corrective quantity for the eventual correction of the pattern data.



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